User Guide



2 After applying leave the mask on the substrate for 30 min. This will

increase the adhesion too. After that

remove the transparent protective foil.

The thin sandblasting-membran remains

on the mask. It will be destroyed during the

Nerview

Substrate Preparation

The surface of the substrate has to be cleaned very carefully. Dust and bigger particles should be removed. The object has to be degreased in order to get the maximum adhesive property. The mask should be handled at room temperature for optimal adhesion. It is possible that there is less adhesion during the heating season. Due to less humidity of the air in winter time it is possible that there is less adhesion of the mask. To increase the adhesion a slight water steam treatment of the mask (after removing the transparent protective foil) is needed. Please notecheck always the adhesion before starting sandblasting.

Preparing the sandblasting mask

transfer paper. Please remove the mask from the transfer paper by pulling upwards. (Transfer paper underneath does not move).





Introduction

The self-stick **SR3000**[™] photoresist film allows you to ransfer your artwork into high detailed stencils for sandblasting on virtually any surface. You can use our photoresist stencils for all brittle materials such as glass, stone, metal, wood and much more.

SR3000[™] photoresist film satisfies all needs for a self-stick film without the problems "self-adhesive" brands can bring. SR3000[™] renders unmatched detail for half-tone imaging and ultra high resolution images. SR3000[™] saves time and money by enabling you to produce a superior product with less hassle

The SR3000[™] is available in:

- · 3MIL for high detailed sandblastings
- 4MII for moderately detailed artwork
- 5MIL for bolder lettering and artwork. Moderate for stage carving on glass
- 9MIL for deep angraving and mostly used for bolder lettering and stage carving on granite

Requirements

A Plastic Burnisher is necessary to bind the processed photomask to the substrate surface and remove the photomask's clear carrier. We can strongly recommend our Wire Wheel Brush; this hand-held tool releases air trapped between the substrate and the photomask.



Sandblasting masks





ABRASIVE IMAGING

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